

Title (en)

PROCESS FOR APPLYING A DECORATIVE LAYER TO A SUPPORT MATERIAL

Publication

EP 0578957 A3 19940810 (DE)

Application

EP 93108914 A 19930603

Priority

DE 4219446 A 19920613

Abstract (en)

[origin: EP0578957A2] In a process for applying a decorative layer consisting of a radiation-curable coating compound, especially of lacquer, adhesive, glue or a mixture of the abovementioned substances or some thereof, to a support plate and/or a web-shaped substrate, the decorative layer being exposed to a high-energy radiation, especially UV radiation, X-ray radiation, laser radiation and/or electron radiation, a particular temperature being maintained at atmospheric pressure, and thereby being cross-linked and/or polymerised, until the decorative layer has achieved a desired hardness, provision is made for the decorative layer which is to be hardened to be masked, in order to provide protection against the action of oxygen, on one side by the support plate forming the substrate and on the other side by a film, for example a carrier film, for the irradiation of the decorative layer to be carried out with a high-energy radiation in an atmosphere free of inert gases, and for a pressure equivalent to atmospheric pressure to be set and to be maintained during the period of action of the high-energy radiation.

IPC 1-7

B44C 5/04; **B32B 27/00**; **B32B 27/04**; **B32B 31/28**

IPC 8 full level

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CPC (source: EP)

B05D 3/061 (2013.01); **B05D 3/068** (2013.01); **B44C 5/0415** (2013.01); **B44C 5/043** (2013.01); **B44C 5/0469** (2013.01)

Citation (search report)

- [X] EP 0216269 A2 19870401 - HOECHST AG [DE]
- [A] EP 0103344 A2 19840321 - ENERGY SCIENCES INC [US]

Cited by

EP1234847A3; RU2621098C2; NL1035423C2; EP3184300A1; EP3184300B1; WO2009139620A3; WO2013092521A1; US9073082B2; EP2927017B1; EP2927017B2

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DOCDB simple family (publication)

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